

Abstract Submitted
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SU-8 Micro-filters Abstract AUBREY HATCH, Brigham Young University — I have designed and flow-tested filters made of the polymer SU-8. SU-8 is a negative epoxy-based photoresist, and the filters are patterned using standard photolithography processes. Pore sizes on the filters have ranged from 5 microns to 20 microns with varying pore geometry. I have successfully removed the SU-8 from the substrate and taken SEM images of the resulting filters. The filters have been flow-tested up to flow rates of 210 mL/min with resulting pressures of up to 0.85 psi.

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